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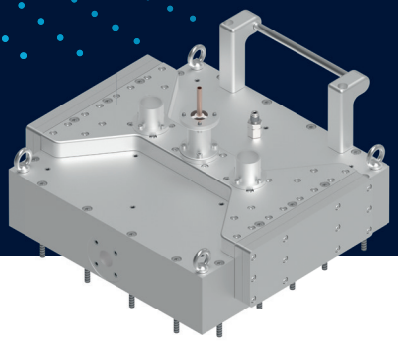
PLASMA ARRAY MA4000Y-013BC

MODULAR PLASMA SYSTEM



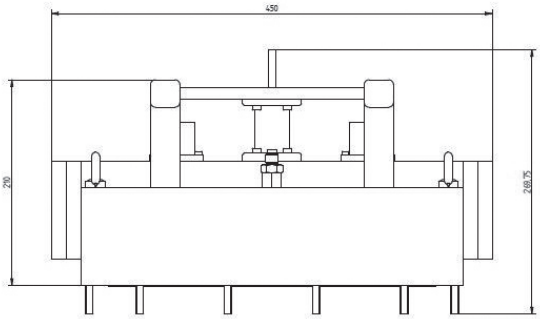
A combination of duo-plasmalines to obtain a two dimensional plasma array.

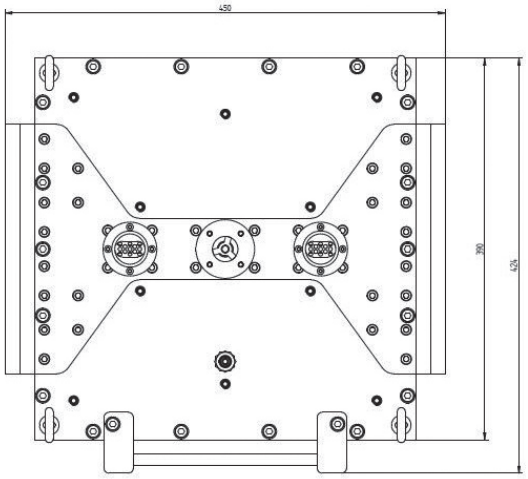
4 parallel arranged plasmalines are combined for plasma assisted surface treatment like surface activating, etching and deposition.

Features

- Low pressure microwave plasma source
- Suitable for cleaning, etching, ashing, deposition, sterilization, pretreatment
- Compact design
- Easy adaption to customer systems
- Integrated gas shower head
- High plasma density
- High efficiency

Outline Dimensions (mm)





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Specifications

Microwave-Power	2000 W cw max.
Frequency	2450 MHz ± 20 MHz
Reactor outlet connector	Plasma Array 320 mm x 320 mm
Primary power circuit	- DC / - A
Primary control	V / - / - A
Efficiency	Approximately 90 % at full output power
Gas connection	Swagelok (SS-4-VCR-1-00032)
Operating pressure	0,5 - 5,0 torr (maximum 5 torr)

Dimensions	Compact design Width: 450 (17,72) mm (inch) Height: 210 (8,27) mm (inch) Depth: 424 (16,69) mm (inch)
Weight	Approximately: 43,3 (95,46) kg (lbs)
Discharge tube	Ceramic
Conditions	In operation: 5 °C (41 °F) - 40 °C (104 °F), relative humidity 80 % to 30 °C (86 °F), above this linearly reduced to 50 %, non-condensing, 3K3 Storage: - 25 °C (- 13 °F) - + 70 °C (158 °F), 70 kPa - 106 kPa, relative humidity 80 % to 30 °C (86 °F), above this linearly reduced to 50 %, non-condensing, 1K3
Prim. heating circuit	- V AC / - Hz / - A
Process gases	O2, N2, H2, F2, Ar, NH3, CF4 and other Fluorine based gases

Recommended system components

- MW-Power supply e.g. MX2000D-171KL
- Magnetron head e.g. MH2000S-250BF